

L Number	Hits	Search Text	DB	Time stamp
-	375	atomic adj layer adj deposition	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/18 09:31
-	40	(atomic adj layer adj deposition) and ((chemical\$3) with (adsorb\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/13 15:36
-	32	((atomic adj layer adj deposition) and ((chemical\$3) with (adsorb\$3))) and oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/13 09:34
-	3	(atomic adj layer adj deposition) and ((chemical\$3) with (adsorb\$3)) and (dilut\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/13 15:37
-	1398	atomic adj layer adj deposition) (ald	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/18 09:32
-	250	(atomic adj layer adj deposition) (ald) and (((aluminum titanium zirconium hafnium tantalum niobium cerium itrium silicon indium ruthenium iridium) adj oxide) ("al.sub.2o.sub.3") ("tio.sub.2") ("zro.sub.2") ("hfo.sub.2") ("ta.sub.2o.sub.5") ("nb.sub.2o.sub.5") ("ceosub.2") ("y.sub.2o.sub.3") ("in.sub.2o.sub.3") ("ruo.sub.2") ("iro.sub.2"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/18 09:41
-	180	(atomic adj layer adj deposition) (ald) and (("sin") ("si.sub.3n.sub.4") ("si.sub.xn.sub.y") ("nbn") ("zrn") ("tan") ("ya.sub.n.sub.5") ("aln") ("gan") ("wn") ("bn"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/18 11:03
-	32	(atomic adj layer adj deposition) (ald) and (("wbn") ("wsin") ("tisin") ("altin"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/18 11:06
-	10	(((atomic adj layer adj deposition) (ald) and (((aluminum titanium zirconium hafnium tantalum niobium cerium itrium silicon indium ruthenium iridium) adj oxide) ("al.sub.2o.sub.3") ("tio.sub.2") ("zro.sub.2") ("hfo.sub.2") ("ta.sub.2o.sub.5") ("nb.sub.2o.sub.5") ("ceosub.2") ("y.sub.2o.sub.3") ("in.sub.2o.sub.3") ("ruo.sub.2") ("iro.sub.2")))) and ((atomic adj layer adj deposition) (ald) and (("srzio.sub.3") ("pbzio.sub.3") ("srruo.sub.3") ("batio.sub.3") ("srzio.sub.3") (ito)))) and ((atomic adj layer adj deposition) (ald) and (("sin") ("si.sub.3n.sub.4") ("si.sub.xn.sub.y") ("nbn") ("zrn") ("tan") ("ya.sub.n.sub.5") ("aln") ("gan") ("wn") ("bn")))) and ((atomic adj layer adj deposition) (ald) and (("wbn") ("wsin") ("tisin") ("altin")))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/18 09:48
-	3	("5976928" "6057231" "6093638").PN.	USPAT	2002/09/18 09:54

-	45	((atomic adj layer adj deposition) (ald) and (((aluminum titanium zirconium hafnium tantalum niobium cerium itrium silicon indium ruthenium iridium) adj oxide) ("al.sub.2o.sub.3") ("tio.sub.2") ("zro.sub.2") ("hfo.sub.2") ("ta.sub.2o.sub.5") ("nb.sub.2o.sub.5") ("ceosub.2") ("y.sub.2o.sub.3") ("in.sub.2o.sub.3") ("ruo.sub.2") ("iro.sub.2")))) and ((atomic adj layer adj deposition) (ald) and (("srtio.sub.3") ("pbtio.sub.3") ("srruo.sub.3") ("batio.sub.3") ("srtio.sub.3") (ito))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/18 10:07
-	26	(((atomic adj layer adj deposition) (ald) and (((aluminum titanium zirconium hafnium tantalum niobium cerium itrium silicon indium ruthenium iridium) adj oxide) ("al.sub.2o.sub.3") ("tio.sub.2") ("zro.sub.2") ("hfo.sub.2") ("ta.sub.2o.sub.5") ("nb.sub.2o.sub.5") ("ceosub.2") ("y.sub.2o.sub.3") ("in.sub.2o.sub.3") ("ruo.sub.2") ("iro.sub.2")))) and ((atomic adj layer adj deposition) (ald) and (("srtio.sub.3") ("pbtio.sub.3") ("srruo.sub.3") ("batio.sub.3") ("srtio.sub.3") (ito)))) and ((atomic adj layer adj deposition) (ald) and (("sin") ("si.sub.3n.sub.4") ("si.sub.xn.sub.y") ("nbn") ("zrn") ("tan") ("ya.sub.n.sub.5") ("aln") ("gan") ("wn") ("bn"))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/18 10:12
-	66	(atomic adj layer adj deposition) (ald) and (("srtio.sub.3") ("pbtio.sub.3") ("srruo.sub.3") ("batio.sub.3") ("srtio.sub.3") (ito)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/18 10:42
-	41	((atomic adj layer adj deposition) (ald) and (("srtio.sub.3") ("pbtio.sub.3") ("srruo.sub.3") ("batio.sub.3") ("srtio.sub.3") (ito))) and @ad<=20010531	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/18 10:42
-	0	((atomic adj layer adj deposition) (ald) and (("sin") ("si.sub.3n.sub.4") ("si.sub.xn.sub.y") ("nbn") ("zrn") ("tan") ("ya.sub.n.sub.5") ("aln") ("gan") ("wn") ("bn")))) and @ad<=05/31/2001	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/18 11:04
-	116	((atomic adj layer adj deposition) (ald) and (("sin") ("si.sub.3n.sub.4") ("si.sub.xn.sub.y") ("nbn") ("zrn") ("tan") ("ya.sub.n.sub.5") ("aln") ("gan") ("wn") ("bn")))) and @ad<=20010531	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/18 11:04
-	19	((atomic adj layer adj deposition) (ald) and (("wbn") ("wsin") ("tisin") ("altin")))) and @ad<=20010531	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/18 11:09
-	50	(atomic adj layer adj deposition) (ald) and (silicide with (aluminum al tungsten w titanium ti cobalt co))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/18 11:11
-	23	((atomic adj layer adj deposition) (ald) and (silicide with (aluminum al tungsten w titanium ti cobalt co))) and @ad<=20010531	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/18 11:11
-	9	((("5112641") or ("5217340") or ("6015590") or ("6042652") or ("6124158"))).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/21 10:33
-	161	(atomic adj layer adj deposition) with (reactor chamber apparatus)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/25 09:51

-	232	(ald (atomic adj layer adj deposition)) with (reactor chamber apparatus)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/25 10:33
-	100	((ald (atomic adj layer adj deposition)) with (reactor chamber apparatus)) and adsorb\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/25 09:53
-	99	((ald (atomic adj layer adj deposition)) with (reactor chamber apparatus)) and adsorb\$3) and (substrates wafers)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/25 09:53
-	3	6042652.URPN.	USPAT	2003/02/25 10:08
-	56	("4058430" "4389973" "4413022" "4416933" "4533410" "4533820" "4689247" "4828224" "4836138" "4846102" "4867952" "4907862" "4913929" "4975252" "4976996" "4993360" "5000113" "5015503" "5077875" "5078851" "5119760" "5156820" "5194401" "5204314" "5270247" "5281274" "5294778" "5304247" "5320680" "5336327" "5484484" "5582866" "5616208" "5693139" "5702530" "5711811" "5749974" "5788447" "5851849" "5876503" "5879459" "5916365" "5935338" "6007330" "6015590" "6042652" "6050216" "6077775" "6090442" "6124158" "6139700" "6143659" "6174377" "6200893" "6270572" "6305314" "2001/0045187").PN.	USPAT USPAT	2003/02/25 10:08 2003/02/25 10:08
-	1	((ale (atomic adj layer adj epitaxy)) with (reactor chamber apparatus)) and ((wafer substrate) with boat)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/25 10:37
-	124	(ale (atomic adj layer adj epitaxy)) with (reactor chamber apparatus)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/25 10:59
-	351	((ald (atomic adj layer adj deposition)) with (reactor chamber apparatus)) or ((ale (atomic adj layer adj epitaxy)) with (reactor chamber apparatus))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/25 10:59
-	69	((ald (atomic adj layer adj deposition)) with (reactor chamber apparatus)) or ((ale (atomic adj layer adj epitaxy)) with (reactor chamber apparatus)) and first with pressure	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/25 11:00
-	11	((ald (atomic adj layer adj deposition)) with (reactor chamber apparatus)) or ((ale (atomic adj layer adj epitaxy)) with (reactor chamber apparatus)) and first with pressure) and (third with pressure)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/25 11:01
-	3	((ald (atomic adj layer adj deposition)) with (reactor chamber apparatus)) or ((ale (atomic adj layer adj epitaxy)) with (reactor chamber apparatus)) and first with pressure) and (third with pressure) with lower	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/25 11:01
-	4	((("6124158") or ("6042652")).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/25 14:52
-	7	6124158.URPN.	USPAT	2003/02/25 14:56

-	6003	(atomic adj layer adj (deposition epitaxy)) ald ale	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/25 15:29
-	45	((atomic adj layer adj (deposition epitaxy)) ald ale) and (first and second and third) with pressure	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/25 15:31
-	1026	((117/88) or (117/89) or (117/102) or (117/202)).CCLS.	USPAT; US-PGPUB	2003/08/25 09:47
-	52	((117/88) or (117/89) or (117/102) or (117/202)).CCLS.) and (ald ale (atomic adj layer adj (epitaxy deposition)))	USPAT; US-PGPUB	2003/03/11 08:10
-	2	((117/88) or (117/89) or (117/102) or (117/202)).CCLS.) and (ald ale (atomic adj layer adj (epitaxy deposition))) and fourth with pressure	USPAT; US-PGPUB	2003/03/11 08:11
-	10	((117/88) or (117/89) or (117/102) or (117/202)).CCLS.) and (ald ale (atomic adj layer adj (epitaxy deposition))) and predetermined with pressure	USPAT; US-PGPUB	2003/03/11 08:11
-	47	((117/88) or (117/89) or (117/102) or (117/202)).CCLS.) and (ald ale (atomic adj layer adj (epitaxy deposition))) and pressure	USPAT; US-PGPUB	2003/03/11 08:12
-	1067	((117/88) or (117/89) or (117/102) or (117/202)).CCLS.	USPAT; US-PGPUB	2003/08/25 09:47
-	59	((117/88) or (117/89) or (117/102) or (117/202)).CCLS.) and (ald ale (atomic adj layer adj deposition) (atomic adj layer adj epitaxy))	USPAT; US-PGPUB	2003/08/25 09:48
-	468	ald and (flush\$3 purg\$3 (inert with pressure))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/28 13:03
-	240	(ald and (flush\$3 purg\$3 (inert with pressure))) and @ad<=20010531	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/28 08:12
-	1	6511539.pn.	USPAT; US-PGPUB	2003/08/28 12:01
-	468	ald and (flush\$3 purg\$3 (inert with pressure))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/28 14:25
-	30	(ald and (flush\$3 purg\$3 (inert with pressure))) and pressure with cycle	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/28 13:29
-	68	(ald and (flush\$3 purg\$3 (inert with pressure))) and first with pressure	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/28 13:32
-	7	((ald and (flush\$3 purg\$3 (inert with pressure))) and first with pressure) and third with pressure	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/28 13:29
-	51	((ald and (flush\$3 purg\$3 (inert with pressure))) and first with pressure) and second with pressure	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/28 13:32

-	442	ald and (flush\$3 purg\$3 (inert with pressure))	USPAT; US-PGPUB	2003/08/28 14:26
-	77	(ald and (flush\$3 purg\$3 (inert with pressure))) and pressure with (steps cycles)	USPAT; US-PGPUB	2003/08/28 14:26